

VARIABLE SURFACE HOT PLATE FOR IMPROVED BAKE UNIFORMITY
OF SUBSTRATES

ABSTRACT OF THE DISCLOSURE

5 A system, method and apparatus are described for
improving critical dimension uniformity in baked
substrates. The system, method and apparatus provide for
varying the distance between a substrate to be baked and
the surface of a hot plate such that an approximately
uniform temperature is obtained in the substrate during
baking. In one embodiment, the substrate is positioned on
a hot plate having a recess generally centered on its top
10 side. The differences in distance between the edges of
the substrates contacting the hot plate and the distance
between the center region of the substrate and the bottom
of the recess enable a generally uniform temperature to
be obtained in the substrate.